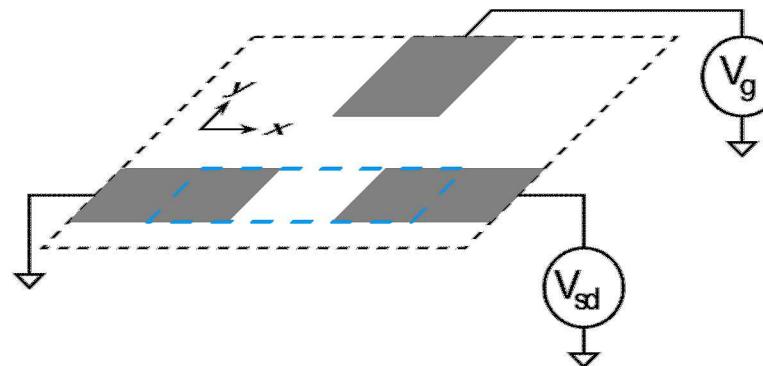
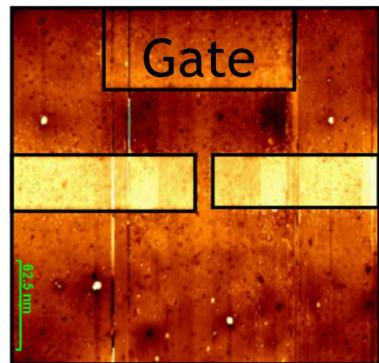
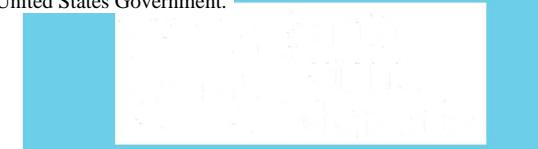


Modeling transport in phosphorus δ -doped silicon tunnel junctions



Leon Maurer, Michael Marshall, DeAnna Campbell, Lisa Tracy,
Tzu-Ming Lu, Daniel Ward, and Shashank Misra

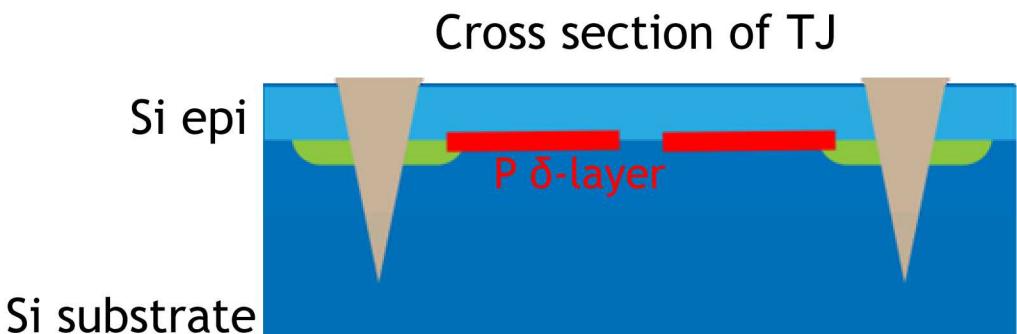
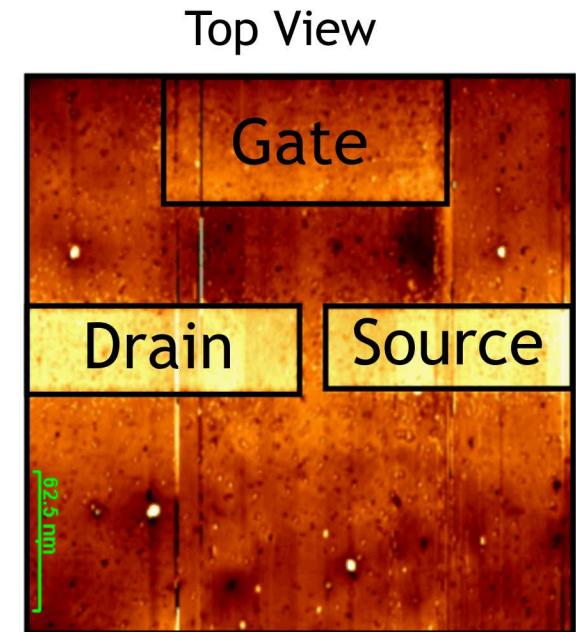


Background

- STM Lithography can produce atomically precise, 2D layers with extremely high doping ($1.7\text{e}14 \text{ cm}^{-2}$) in Si
- Potential use in fabricating a variety of electrical devices
- Very high doping -> does not act like normal Si!
- Requires relatively low fabrication temperatures -> tricky fabrication
- Currently making test structures, including tunnel junctions, to better understand fabrication and δ -layer properties
- Investigating:
 - Simple models for transport
 - Effects of impurities

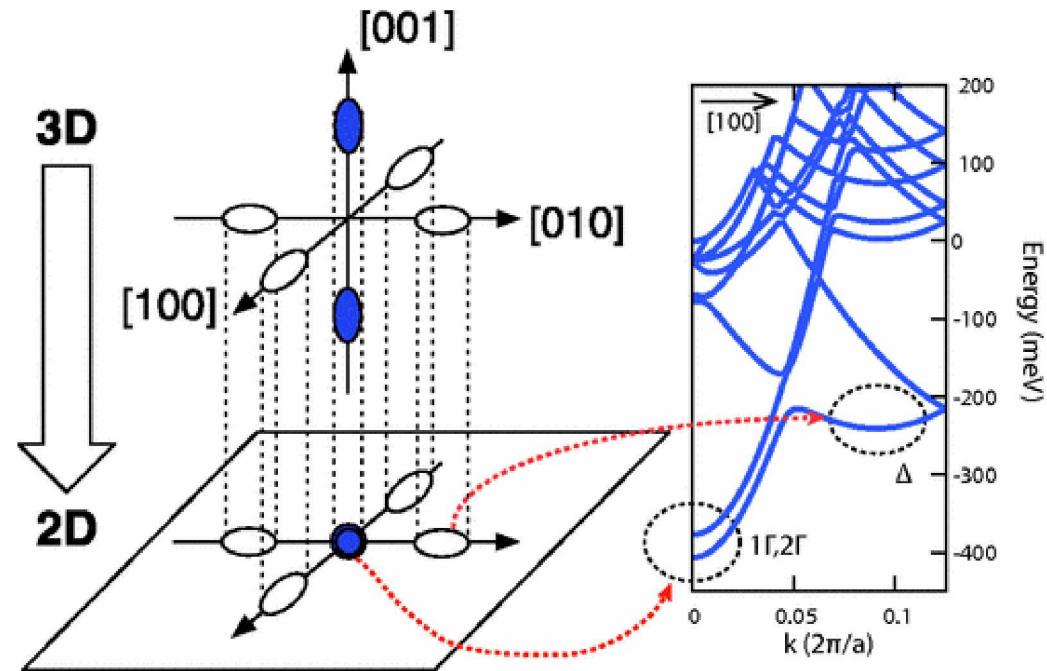
STM lithography and δ -layers

- Technique pioneered by Lyding and Simmons, now also done at Sandia and NIST
- STM lithography gated tunnel junction shown
- Fast fabrication facts
 - Uses hydrogen attached to Si substrate as a mask
 - P attached to $\sim 1/4$ of unmasked Si ($\sim 1.7 \times 10^{14}$ P atoms/cm $^{-2}$)
 - 30 nm of epitaxial Si grown on top
- P confined to few-monolayer-thick “ δ -layer”



Mysterious properties of phosphorus δ -doped silicon

- Not bulk Si band structure!
- Hard to measure band structure of buried, disordered alloy
- Table: predicted band minima and Fermi level for quarter-layer doped δ -layer sheets (meV below Si conduction-band minimum)
- No consensus!

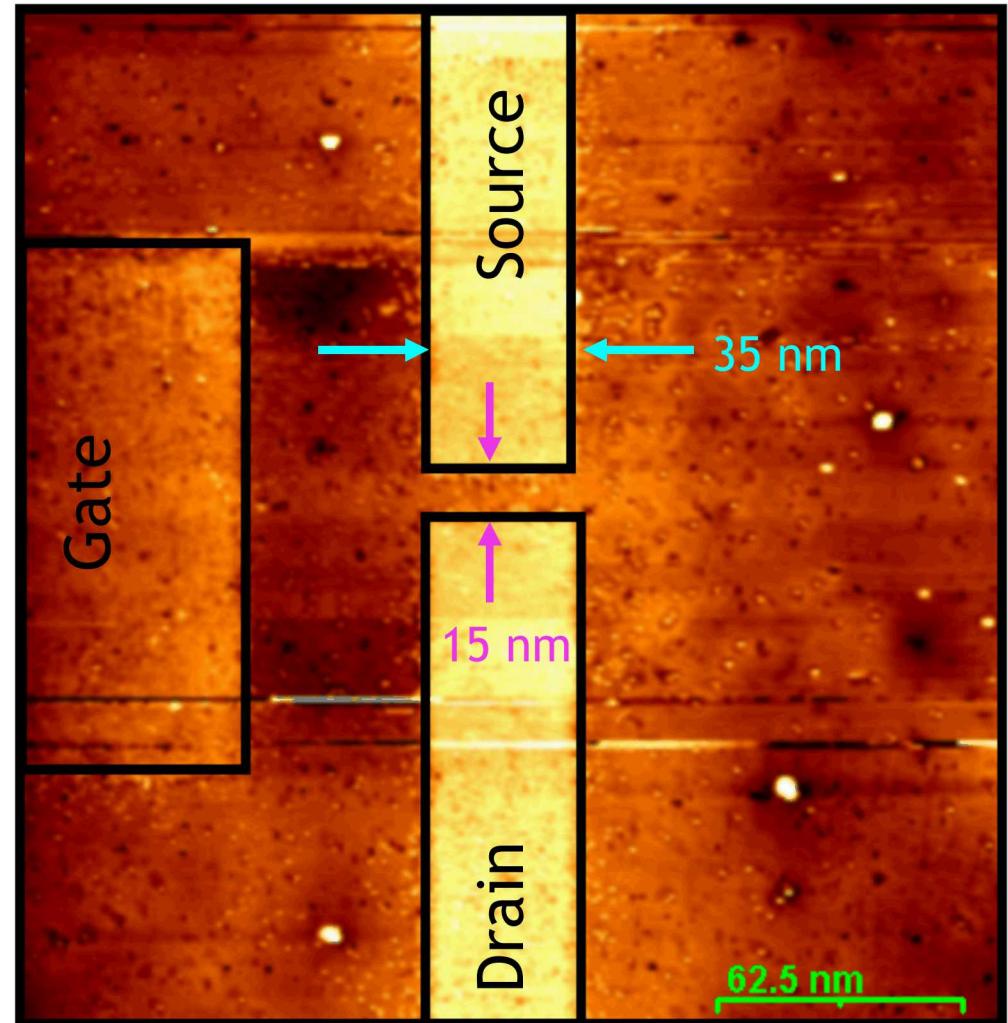


1. D. J. Carter et al., *Nanotechnology*, **22**, 065701 (2011).
2. D. W. Drumm et al., *Nanoscale Res. Lett.*, **8**, 111 (2013).
3. H. Ryu et al., *Nanoscale*, **5**, 8666 (2013). S. Lee et al., *Phys. Rev. B*, **84**, 205309 (2011).
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Model	E_{Γ_1}	E_{Γ_2}	E_{Δ}	E_F
DFT (1D) [1]	296	288	165	72
DFT (3D) [2]	369	269	68	23
TB (3D) [3]	401	375	249	115
DFT (1D) [4]	419	394	250	99
TB (3D) [5]	427	421	287	142

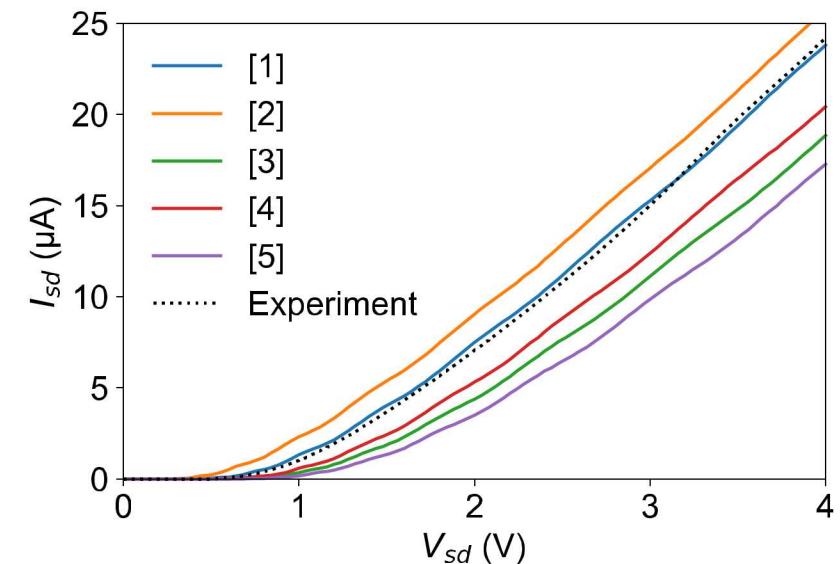
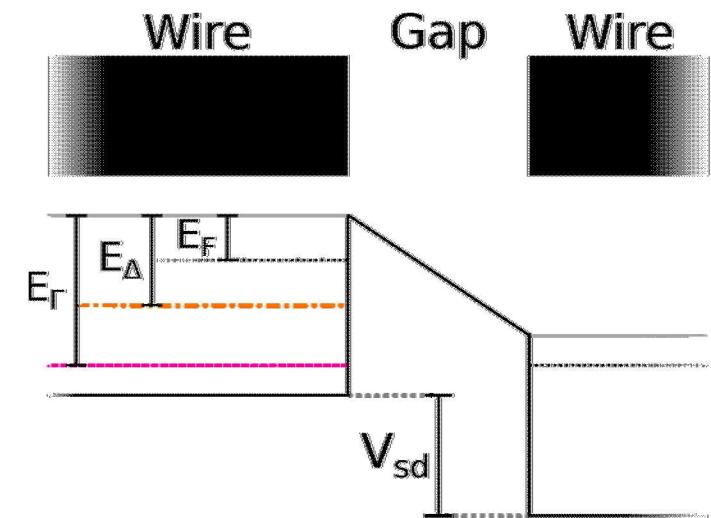
Our tunnel junctions

- Useful for testing fabrication and models
- Can be made with or without inplane or top gate
- Consider 35-nm-wide wire with a 15-nm-wide gap
- Effective mass theory for electrons



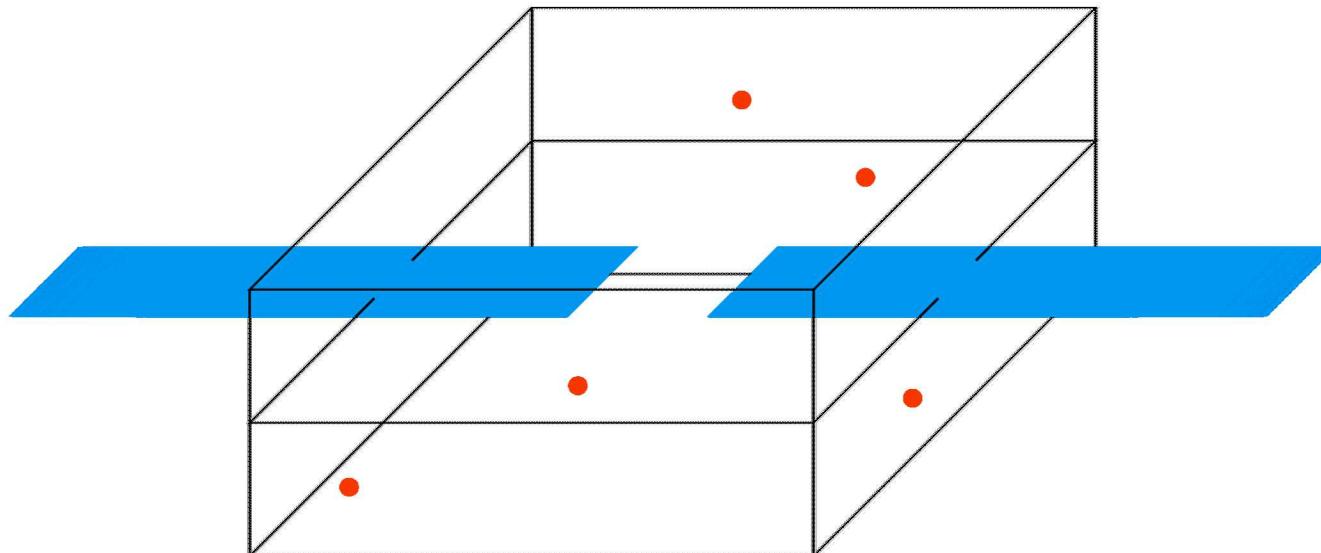
One-dimensional model: band structure revealed?

- Trapezoidal barrier from linear voltage drop and band offsets
- Calculate transmission/currents for all bands
- I-V curves for all parameters in Table as well as experimental data (dotted). $78\text{ k}\Omega$ resistance in series
- Takeaways:
 - Even simple model produces reasonable results
 - Band structure matters
- Does this mean we now know the band structure?



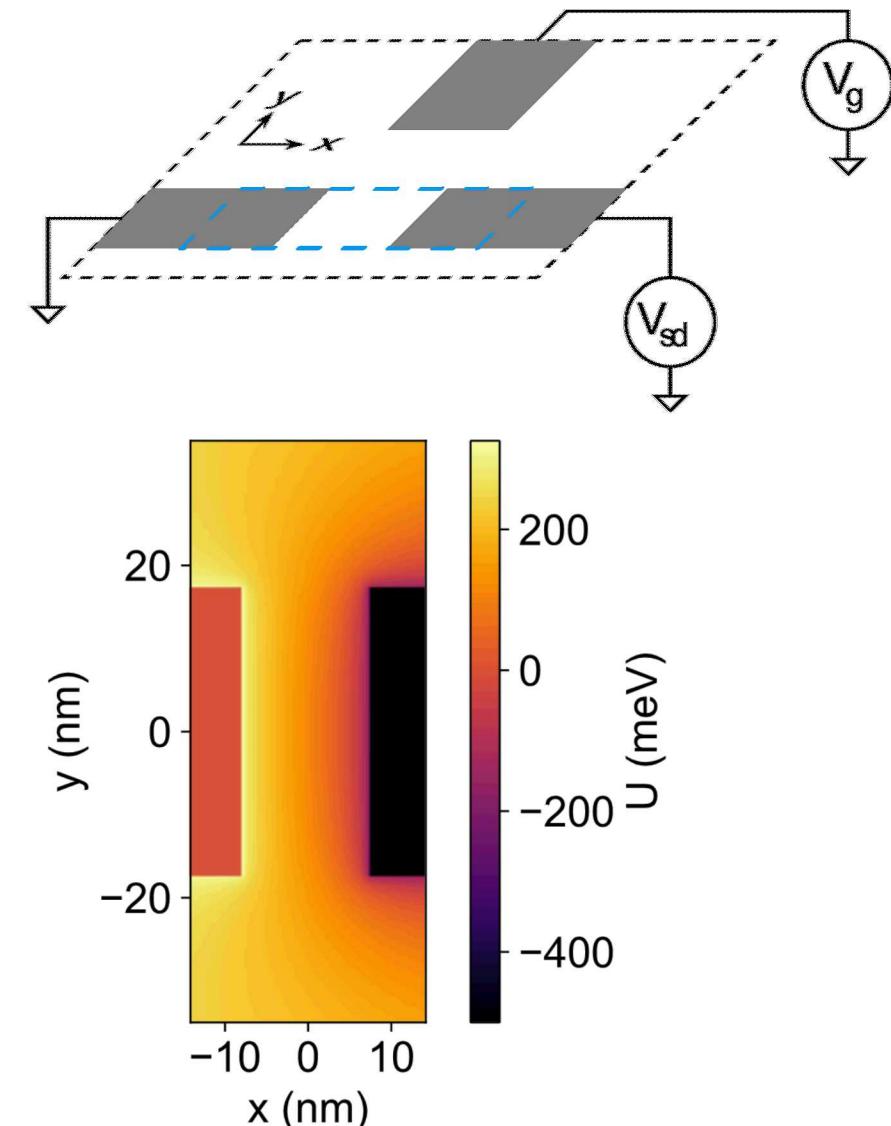
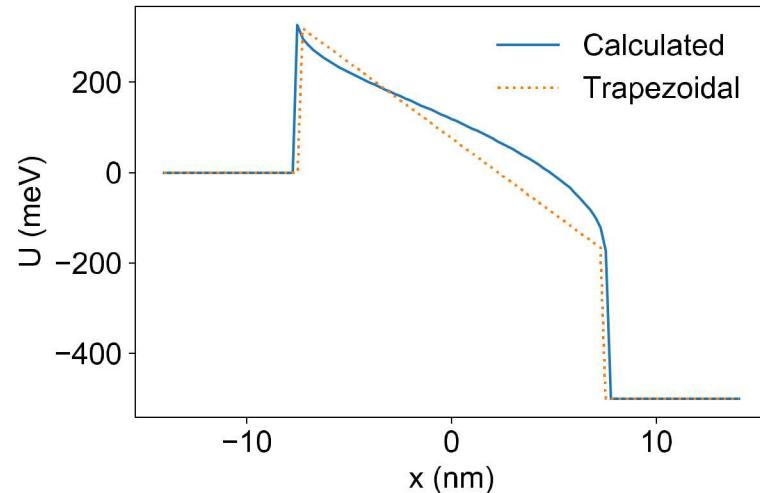
Stray charges

- Unfortunately, devices have defects
- Concerned with stray charges in Si grown above δ -layer
- Need model that can handle real electrostatics, including randomly located stray charges near the junction



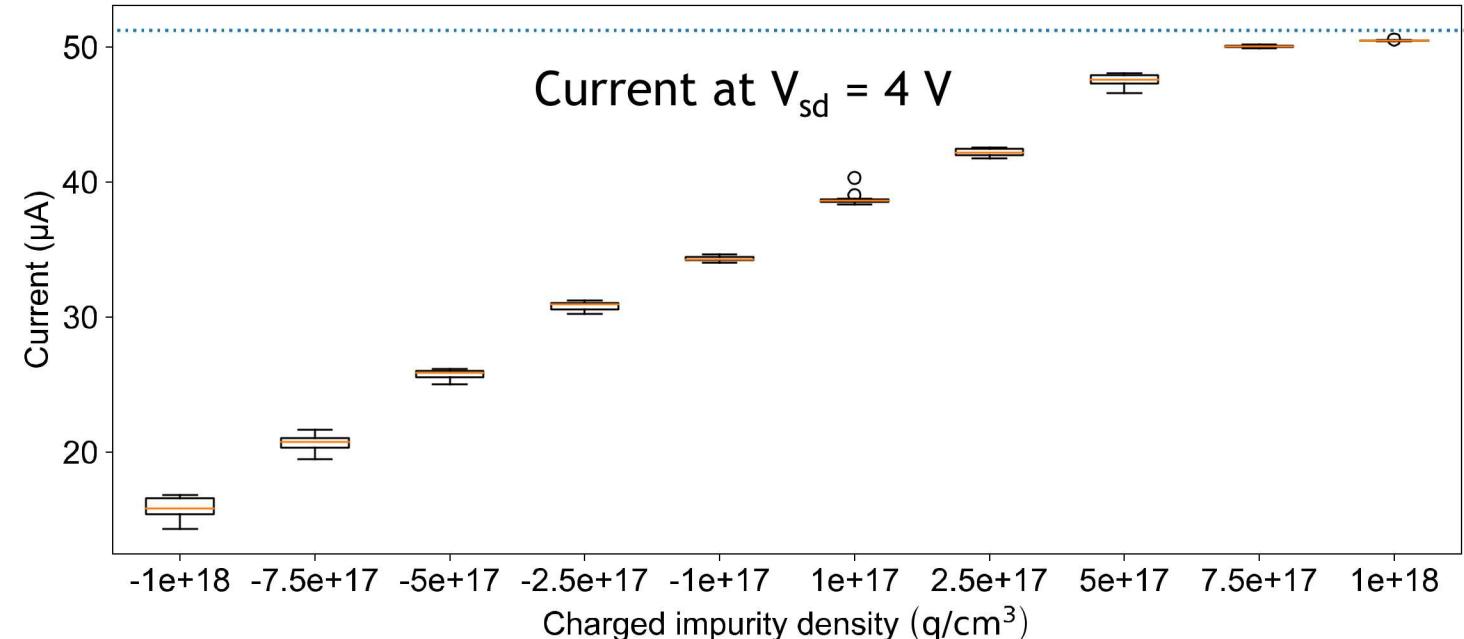
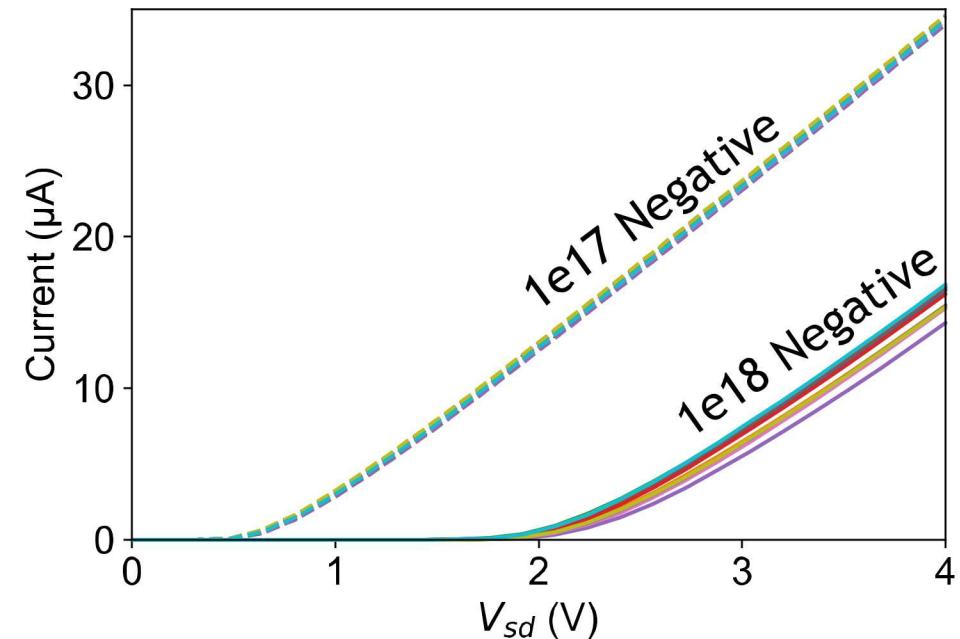
Two-dimensional model with electrostatics

- Treat δ -doped regions as perfect conductors, partially screen stray charges
- Electrostatics with boundary element method
- Kwant package to calculate transmission
- $78 \text{ k}\Omega$ resistance and band structure from [1]
- Can also include gates



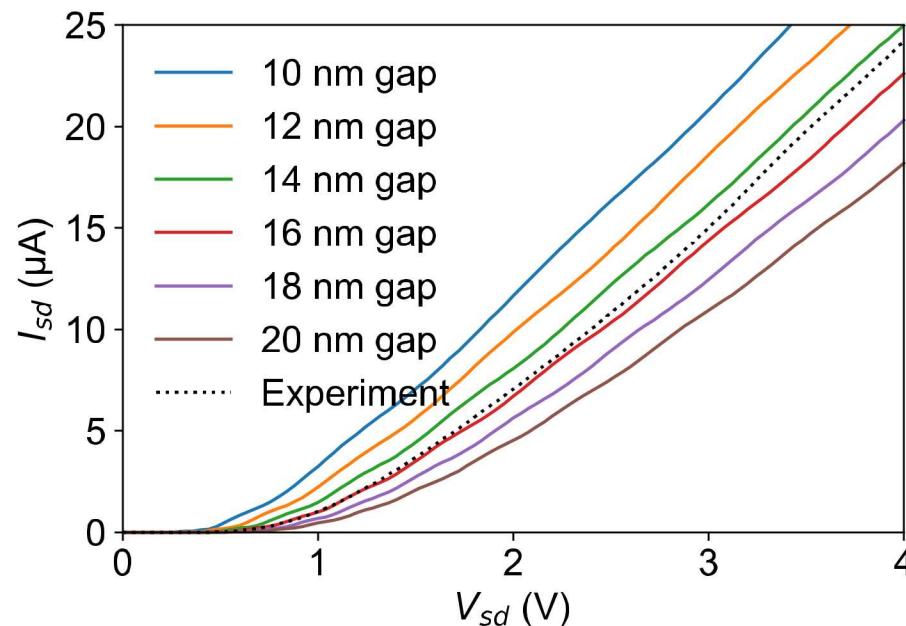
9 Stray charges as spoilers

- Considered negative and positive stray charges with varying densities (in cm^{-3})
- 10 runs for each stray charge density
- Main effect: turn on voltage (similar magnitude to band structure choice)
- Some effect on variability



Conclusions

- Simple models are promising way to understand δ -doped devices
- Stray charges have effects comparable to band structure choice
- Imperfections in geometry also important
- Several good junctions could nail down the band structure



Effect of gate

- 2D model can handle more complicated devices
- Example of inplane gate
- Model predicts gate more effective than seen in experiment
- Unclear why. Reproducibility issues with our devices.

